

	Type	L #	Hits	Search Text	DBs
1	BRS	L1	16521	(film or layer or films or layers) near3 target	US- PGPUB; USPAT
2	BRS	L2	2191	1 same chamber	US- PGPUB; USPAT
3	BRS	L3	1423	1 near10 (gas or gases)	US- PGPUB; USPAT
4	BRS	L4	591	3 same (substrate)	US- PGPUB; USPAT
5	BRS	L5	39366	(silicon adj2 nitride) adj2 (film or layer)	US- PGPUB; USPAT
6	BRS	L6	3667	5 near15 (gas or gases)	US- PGPUB; USPAT
7	BRS	L7	14	4 same 6	US- PGPUB; USPAT
8	BRS	L8	3	7 same chamber	US- PGPUB; USPAT
9	BRS	L9	40	1 same 6	US- PGPUB; USPAT
10	BRS	L10	10	9 same chamber	US- PGPUB; USPAT
11	BRS	L11	6	substrat same chamber	US- PGPUB; USPAT

	Type	L #	Hits	Search Text	DBs
12	BRS	L12	63325	substrate same chamber	US-PGPUB; USPAT
13	BRS	L13	1262	1 same 12	US-PGPUB; USPAT
14	BRS	L14	3	6 same 13	US-PGPUB; USPAT
15	BRS	L15	40920	(silicon adj2 nitride) adj2 (film or layer or films or layers)	US-PGPUB; USPAT
16	BRS	L16	143	15 near3 target	US-PGPUB; USPAT
17	BRS	L17	70	16 same substrate	US-PGPUB; USPAT
18	BRS	L18	29	17 same chamber	US-PGPUB; USPAT
19	BRS	L19	19143	(silicon adj2 nitride) adj2 (film or layer or films or layers)	USOCR; EPO; JPO; DERWE NT; IBM_TDB

	Type	L #	Hits	Search Text	DBs
20	BRS	L20	18	19 near3 target	USOCR; EPO; JPO; DERWE NT; IBM_TD B
21	BRS	L21	2	16 near20 (after or before) near20 substrate	US- PGPUB; USPAT
22	BRS	L22	492	silicon adj2 nitrided	US- PGPUB; USPAT
23	BRS	L23	492	silicon adj2 nitrided	US- PGPUB; USPAT
24	BRS	L24	97861	silicon adj2 nitride	US- PGPUB; USPAT
25	BRS	L25	9	nitrogen near10 24 near10 (disilane or trisilane)	US- PGPUB; USPAT
26	BRS	L26	2165	24 near5 (plasma adj2 cvd)	US- PGPUB; USPAT